## **REMARKS/ARGUMENTS**

Applicants note the discussion with Examiner Wille concerning the above-identified application, in particular the Final status of the outstanding Official Action. During this discussion Examiner Willie kindly indicated that the indication of Finality was in error, and that the Office Action Summary was correct in indicating that the present Action is non-final.

Applicants note the Examiner's reticence in complying with Office Policy regarding the present IDS situation. The Examiner is strongly encouraged to discuss this situation with his Supervisors. Special consideration has been given in this series of "bulk filing" cases, and the IDS procedures in this case has been specifically approved by the Office. It is not within the Examiner's ambit to ignore this situation. Applicants do not want this issue to escalate, nor do they wish to file a Petition. Thus, the Examiner is respectfully requested to contact the undersigned, if necessary, or to discuss this case and the Office-approved bulk filing IDS procedures with, e.g., SPE Baumeister.

The rejection of Claims 1-4 and 6-9 as anticipated by <u>Guenzer</u> is traversed.

The Examiner points to the "cover Figure," which is Figure 2 of the reference, and inverts the structure, alleging applicability to the present claims. However, even if inverted, the structure shown by the reference does not describe the presently claimed strain-relief layer comprising an amorphous oxide material in contact with the monocrystalline silicon substrate. Rather, and as acknowledged at the bottom of page 2 of the Official Action, the reference shows an alkaline earth-BTO layer in contact with silicon layer 14. In this regard, note the description in, e.g., pending Claim 1 regarding a strain-relief layer and its particular constitution: the strain-relief material layer comprises an amorphous oxide material in contact with the monocrystalline silicone substrate, and a monocrystalline metal oxide selected from a particular group contacting the amorphous oxide material. As this structure is now shown in Guenzer, the anticipation rejection should be withdrawn.

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The rejection of Claims 10-14 under 35 U.S.C. 103(a) as being unpatenable over

Guenzer in view of Grudkowsky is traversed, for at least those same reasons noted above.

As discussed immediately above, Guenzer fails to show the presently claimed

monolithic semiconductor-piezo electric structure comprising a substrate, a strain-relief

material layer, etc. At paragraph 11 of the Official Action, it is admitted that Guenzer does

not specify a device structure. Grudkowsky fails to make up for that lacking in Guenzer, as

it, too, fails to disclose or suggest the underlying semi-conductor piezoelectric structure

presently claimed. For these reasons, this rejection should be withdrawn, as should the

obviousness rejection over Guenzer in view of Kittel, as Kittel similarly fails to correct the

deficiencies of Guenzer.

In view of the above, Applicants respectfully request the full consideration of the IDS

as submitted herein in accordance with Office Policy, and the passage of this case to Issue.

Respectfully submitted,

OBLON, SPIVAK, MCCLELLAND

MAIER & NEUSTADT, P.C.

Customer Number 22850

Tel: (703) 413-3000

Fax: (703) 413 -2220 (OSMMN 06/04) Richard L. Treanor Attorney of Record Registration No. 36,379

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